

VPG200 exposure parameters

Ref plate: 28 mJ/cm²

Cr blank - Nanofilm SL (Soda Lime), Cr 90nm, PR AZ1512 530nm

Updated: GAR / 14th May 2018

illumination Factor	[mJ/cm ²]	oct. 16 - 8. Jan 18	Jan- April 18
Fast	20mm	58.3	130
Standard	10mm	233.3	310
Advanced	4mm	373.3	220

Example: AZ ECI 600nm on Si; i-line dose 90 mJ/cm ²
154.29% or 77% at speed 0.5
38.57%
24.11%

mode	Write Head	110x110 mm ²		Optical Focus [%]	Pneumatic Focus [%]	Intensity [%]	CDBias ZX [nm]	CDBias ZY [nm]	Throughput (including handling) [5" mask/hour]
		Beam Spot [nm]	Speed [mm ² /min]						
Fast	20mm	1800	1960	NA	0	48.0%	-50	-200	7
Standard	10mm	900	980	On demand	8	12.0%	-50	-100	3.7
Advanced	4mm	550	190	On demand	40	7.5%	-50	-150	0.9

Standard mask fab process (Order Cr-blank(s) at least 24 hours before booking)

- Step 01 Convert your design using left hand linux workstation (no booking, no login)
- Step 02 Expose: VPG200 student/carrier wizard mode with above parameters
- Step 03 Develop - etch Cr - stripp resist Hamatech zone 06